

CLAIMS

1. An apparatus characterized by comprising a reaction chamber forming a space in which a substrate is to be processed, a gas supply pipe which is connected to said reaction chamber and which supplies processing gas for said substrate, and a gas exhaust pipe for exhausting an inside of said reaction chamber, wherein

a gas reservoir for storing gas to be supplied to said reaction chamber and a bypass line which bypasses said gas reservoir are juxtaposed to each other in a portion of said gas supply pipe, and

said substrate processing apparatus further comprises a control unit which allows the processing gas to be supplied to said reaction chamber using one of said gas reservoir and said bypass line when said substrate is processed.